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PATENT APPLICATION
Do. No. 4234-8

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Dong-Ho KIM et al.

Serial No. 09/693,409

Examiner: D. Rutledge

Filed: October 19, 2000

Group Art Unit: 2851

For: SEMICONDUCTOR MANUFACTURING APPARATUS FOR
PHOTOLITHOGRAPHIC PROCESS

Box Non-Fee Amendment

Assistant Commissioner for Patents
Washington, D.C. 20231

BH/pmd/A
3/9/cr
RLBm

RESPONSE TO OFFICE ACTION

Responsive to the Office Action, dated October 17, 2001, please amend the application as follows.

IN THE CLAIMS

Please amend the claims as follows:

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1. (Once amended) A semiconductor manufacturing apparatus for a photolithographic process including a coating process and a developing process, the apparatus comprising:
 - a first port where a substrate comes in and goes out;
 - a second port, having a constant distance from the first port, where the substrate comes in and goes out;
 - coating means for performing the coating process; and
 - developing means for performing the developing process, the developing means being stacked in parallel with the coating means,wherein the coating means includes:

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